## Unusual 1,3-Rearrangement of Trimethylsilyl Group in the Reaction of 2,4,6-Tris[bis(trimethylsilyl)methyl]phenyllithium

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Summary; 2,4,6-Tris[bis(trimethylsilyl)methyl]phenyllithium (TbLi) gave a novel 1,3-silicon rearrangement product above -30 °C, while the treatment of TbLi with some electrophiles also afforded 1,3-silicon rearrangement products even at -78 °C probably *via* single electron transfer mechanism.

Rearrangement reactions with migration of silicon atom have attracted much attention from a standpoint of not only the mechanistic interest but also their potential synthetic utility.<sup>1</sup> Among them are a variety of 1,3-migration reactions of a silyl group from heteroatom to carbon (or *vice versa*) or heteroatom to heteroatom.<sup>2</sup> However, there has been no established example of 1,3-silyl group shift from carbon to carbon except for the thermal 1,3-sigmatropic rearrangement of allylsilanes in the high temperature (500 °C) gas phase reactions<sup>3</sup> and the photochemical 1,3-silicon migration of benzylsilanes<sup>4a</sup> and allylsilanes.<sup>4b</sup>

We have recently reported that 2,4,6-tris[bis(trimethylsilyl)methyl]phenyl (denoted as **Tb** hereafter in this paper) is a usuful protective group for kinetic stabilization of highly reactive species such as *N*-thiosulfinylaniline (Tb-N=S=S),<sup>5</sup> and also estimated the bulkiness of this new sterically demanding group by the enolate formation reaction using TbLi as a base.<sup>6</sup> Here we have investigated the thermal stability and some reactivity of TbLi and found an unusual 1,3-silicon rearrangement in this unique polysilylated bulky aryllithium.



When a light yellow THF solution of **TbLi** generated by lithiation of **TbBr** with 2.2 eq. of *t*-BuLi (1.6 N in pentane) at -78 °C was treated with an excess amount of deuterium oxide ( $D_2O$ ) at this temperature, only **TbD** was isolated in 98% yield.

TbBr 
$$\xrightarrow{t-BuLi}$$
 [TbLi]  $\xrightarrow{t}$  TbLi  $\xrightarrow{t}$  TbH  $\xrightarrow{t}$  63% 30%  
D<sub>2</sub>O  $\xrightarrow{t}$  1a + TbH  $\xrightarrow{t}$  63% 30%  
D<sub>2</sub>O  $\xrightarrow{t}$  1a + TbH + TbD  $\xrightarrow{t}$  1a + TbH + TbH  $\xrightarrow{t}$  1a + TbH + TbH  $\xrightarrow{t}$  1a + TbH + TbD  $\xrightarrow{t}$  1a + TbH + TbH + TbD = 1a + TbH + TbH + TbD = 1a + TbH + TbD = 1a + TbH + TbD = 1a + TbH + T

 $D_2O$  addition to the **TbLi** solution at -30 °C also resulted in a quantitative formation of **TbD**. On the other hand, 63% of deuterated phenylsilane derivative **1a** (E=D) was obtained along with 30% of **TbH** by  $D_2O$  addition at room temperature to an orange colloidal solution of the anion.



The formation of unusual rearranged product 1a represents the first example of 1,3-anionic silicon rearrangement from carbon to carbon and is most likely interpreted in terms of the liability of a silicon atom to highcoordination leading to pentacoordinated silicon intermediate 3. Since a 7:3 mixture of **TbH** and **TbD** (total 84%) was isolated together with 11% of 1a by D<sub>2</sub>O quenching at -20 °C, the 1,3-silicon rearrangement of **TbLi** is considered to compete with its proton abstraction reaction from THF leading to the **TbH** formation at the temperature range where the rearrangement becomes feasible.

$$\frac{\Delta}{-78 \cdot C_{-r.t.}} \xrightarrow{PhCH_{2}Br} \underline{1b} + \underline{1c} + TbH$$

$$-78 \cdot C_{-r.t.} \xrightarrow{r.t.} 78\% 3\% 25\%$$
1. PhCH\_{2}Br
$$-78 \cdot C/10 h$$
2. D<sub>2</sub>O/-78 · C 1b + TbD + TbBr + (PhCH<sub>2</sub>)<sub>2</sub>
2. D<sub>2</sub>O/-78 · C 4\% 29% 66\% 28\%
1. PhCH<sub>2</sub>Cl
$$-78 \cdot C/10 h$$
2. D<sub>2</sub>O/-78 · C 1b + TbH + TbD + (PhCH<sub>2</sub>)<sub>2</sub> + PhCH<sub>2</sub>CHPh
$$4\% \underbrace{9:1}_{total} 1 7\% \underbrace{5}_{43\%}$$

The rearranged benzyl anion 4 readily reacted with benzyl bromide at room temperature to give the corresponding coupling product 1b (E=CH<sub>2</sub>Ph)<sup>7</sup> in 78% yield together with 1c (E=H, 3%)<sup>8</sup> and TbH (25%). On the contrary, treatment of the TbLi solution with benzyl bromide at -78 °C for 10 h followed by D<sub>2</sub>O quenching

at this temperature afforded unexpected products such as 1b (4%), TbD (29%), TbBr (66%), and bibenzyl (28%). The reaction of TbLi with benzyl chloride under similar reaction conditions also gave 1b (4%) along with a 9:1 mixture of TbH and TbD (total 94%), bibenzyl (7%), and 1-chloro-1,2-diphenylethane 5 (43%).



Taking account of the aforementioned stability of **TbLi** alone in THF even at -30 °C, the formation of the rearranged product **1b** by the treatment of **TbLi** with benzyl halides at -78 °C led us to propose an electron transfer reaction mechanism including the generation of **Tb** radical and its subsequent 1,3-silicon rearrangement and recombination with coexisting benzyl radical as shown in Scheme II. The formation of **TbBr** and bibenzyl derivatives is also consistently explained by further reactions of **Tb** radical with the counterpart anion radicals as shown in Scheme II, in which the relative stability of the resulting anions such as 6 and 7 and the higher reactivity of bromine than chlorine atom toward a radical are probably responsible for the dichotomy in the reaction pathway (*i. e.*, hydrogen *vs.* halogen abstraction).



Similar 1,3-silicon rearrangement product  $8^9$  was obtained in 20% yield by treatment of TbLi with phenyltrichlorosilane followed by reduction using lithium aluminum hydride, while only the normal coupling product 910 (9%) was isolated without any amount of rearranged products in the case of phenyltrichlorogermane. The difference between PhSiCl<sub>3</sub> and PhGeCl<sub>3</sub> is probably due to the longer bond length of C-Ge than C-Si which allows the direct attack of **Tb** radical or anion to the germanium atom in spite of its steric bulkiness. Acknowledgement: We are grateful to Shin-etsu Chem. Co. Ltd. for the gift of chlorosilanes. This work was partly supported by the Grant-in-Aid for Scientific Research (No. 02804039) from the Ministry of Education, Science, and Culture of Japan.

## **References and Notes**

1. a) A.G. Brook, Acc. Chem. Res., 7, 77 (1974); b) A. G. Brook and A. R. Bassindale, "Molecular Rearrangements of Organosilicon Compounds", Essay 9 in "Rearrangements in Ground and Excited States", Ed. P. de Mayo, Academic Press, New York (1980).

2. a) A. G. Brook and D. G. Anderson, Can. J. Chem., 46, 2115 (1968); b) E. Block, "Reactions of Organo-sulfur Compounds", Academic Press, New York (1978); c) E. Vedejs and M. Mullins, Tetrahedron Lett., 2017 (1975); d) A. G. Brook, D. M. MacRae, and W. W. Limburg, J. Am. Chem. Soc., 89, 5493 (1967); e) A. G. Brook, J. Organomet. Chem., 86, 185 (1975); f) G. L. Larson and Y. V. Fernandez, J. Organomet. Chem., 86, 183 (1975); d) H. Kwart and W. E. Barnett, J. Am. Chem. Soc., 99, 614 (1977).

3. a) H. Kwart and J. Slutsky, J. Am. Chem. Soc., 94, 2515 (1972); b) J. Slutsky and H. Kwart, J. Am. Chem. Soc., 95, 8678 (1973).

4. a) M. Kira, H. Yoshida, and H. Sakurai, J. Am. Chem. Soc., 107, 7767 (1985); b) M. Kira, T. Taki, and H. Sakurai, J. Org. Chem., 54, 5647 (1989).

5. R. Okazaki, M. Unno, and N. Inamoto, Chem. Lett., 1987, 2293.

6. R. Okazaki, M. Unno, and N. Inamoto, Chem. Lett., 1989, 791.

7. **1b**; white crystals, mp. 118-119 °C; <sup>1</sup>H-NMR(CDCl<sub>3</sub>)  $\delta$  -0.058(s, 9H), 0.014(s, 9H), 0.023(s, 9H), 0.073 (s, 18H), 0.19(s, 9H), 1.34(s, 1H), 2.17(s, 1H), 2.84(H<sub>X</sub>, J<sub>AX</sub> = 9.0 Hz, J<sub>MX</sub> = 6.3 Hz, 1H), 2.96(H<sub>M</sub>, J<sub>AM</sub> = 13.8 Hz, J<sub>MX</sub> = 6.3 Hz, 1H), 3.15(H<sub>A</sub>, J<sub>AM</sub> = 13.8 Hz, J<sub>AX</sub> = 9.0 Hz, 1H), 6.32(brs, 1H), 6.66(brs, 1H), 7.00-7.16(m, 5H); <sup>13</sup>C-NMR(CDCl<sub>3</sub>)  $\delta$  -1.47(q), 0.61(q), 0.78(q), 0.94(q), 6.05(q), 27.45(d), 30.16(d), 36.39(d), 40.06(t), 122.24(d), 125.76(d), 127.97(d), 128.01(d), 129.00(d), 129.56(s), 141.97(s), 143.23(s), 150.53(s), 152.34(s); MS, m/z 642(M<sup>+</sup>, 5%), 481(7), 73(100); HRMS, m/z 642.3759, calcd for C<sub>34</sub>H<sub>66</sub>Si<sub>6</sub> 642.3779.

8. 1c; white crystals, mp. 102-103 °C; <sup>1</sup>H-NMR(CDCl<sub>3</sub>)  $\delta$  0.014(s, 27H), 0.025(s, 18H), 0.36(s, 9H), 1.27 (brs, 1H), 2.19(brs, 1H), 2.25(s, 2H), 6.26(brs, 1H), 6.38(brs, 1H); <sup>13</sup>C-NMR(CDCl<sub>3</sub>)  $\delta$  -0.55(q), 0.61(q), 0.71(q), 5.67(q), 27.26(d), 27.39(t), 29.70(d), 123.52(d), 127.31(d), 128.56(s), 142.96(s), 147.67(s), 150.03(s); MS, m/z 552(M<sup>+</sup>, 12%), 537(2), 479(4), 464(8), 73(100); HRMS, m/z 552.3309, calcd for C<sub>27</sub>H<sub>60</sub>Si<sub>6</sub> 552.3309.

9. 8; white crystals, mp. 90-92 °C; <sup>1</sup>H-NMR(CDCl<sub>3</sub>)  $\delta$  0.028(s, 9H), 0.036(s, 9H), 0.061(s, 9H), 0.078(s, 18H), 0.29(s, 9H), 1.33(s, 1H), 2.24(s, 1H), 2.38(t, J = 5.0 Hz, 1H), 4.53(d, J = 5.0 Hz, 1H), 4.57(d, J = 5.0 Hz, 1H), 6.30(brs, 1H), 6.65(brs, 1H), 7.23-7.44(m, 5H); <sup>13</sup>C-NMR(CDCl<sub>3</sub>)  $\delta$  -0.19(q), 0.63(q), 0.73 (q), 0.76(q), 5.93(q), 22.38(d), 27.34(d), 30.03(d), 122.74(d), 127.50(d), 127.82(d), 129.56(d), 133.22(s), 135.62(d), 143.73(s), 145.31(s), 149.50(s), 151.14(s); MS, m/z 658(M<sup>+</sup>, 25%), 633(7), 585(35), 73(100); HRMS, m/z 658.3542, calcd for C<sub>33</sub>H<sub>66</sub>Si<sub>7</sub> 658.3548; these spectral data are undoubtedly different from those of TbSiH<sub>2</sub>Ph which can be synthesized by the nucleophilic phenyl substitution of TbSiF<sub>3</sub> followed by LiA1H<sub>4</sub> reduction.

10. 9; white crystals, mp. 134-136 °C; <sup>1</sup>H-NMR(CDCl<sub>3</sub>)  $\delta$  -0.03(s, 36H), 0.04(s, 18H), 1.32(s, 1H), 2.11(s, 2H), 5.14(s, 2H), 6.35(brs, 2H), 7.3-7.6(m, 5H); MS, m/z 704(M<sup>+</sup>, 33%), 615(25), 552(33), 73(100); HRMS, m/z 704.2990, calcd for C<sub>33</sub>H<sub>66</sub>Si<sub>6</sub>Ge 704.2990.

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